

Contents

CONTRIBUTORS	ix
PREFACE	xi

PART I. INTRODUCTION

1 Preparation and Property Correlations in Thin Films

K. N. Tu and R. Rosenberg

PART II. VARIATION OF MICROSTRUCTURE OF THIN FILMS

2 Molecular Beam Epitaxy of Superlattices in Thin Films

A. C. Gossard

I. Introduction	13
II. Molecular Beam Epitaxy	15
III. Structure of Semiconductor Superlattices	20
IV. Properties of Superlattice Structures	36
V. Concluding Remarks	59
References	61

3 Epitaxial Growth of Silicon Structures—Thermal, Laser-, and Electron-Beam-Induced

S. S. Lau and J. W. Mayer

I. Introduction	67
II. Thermal and Laser-Induced Epitaxy: Implanted-Amorphous Silicon	72
III. Deposited Layers of Silicon on Silicon	81
IV. Epitaxial Silicides	92
V. Crystallization of Deposited Films	99
VI. Summary	107
References	108

4 Characterization of Grain Boundaries in Bicrystalline Thin Films

F. Cosandey and C. L. Bauer

I. Introduction	114
II. Structure of Grain Boundaries	116
III. Properties of Grain Boundaries	124
IV. Preparation of Bicrystalline Thin Films	130
V. Characterization of Grain Boundary Structure	134
VI. Recent Experimental Results	143
VII. Summary	156
VIII. Perspective	156
References	157

5 Mechanical Properties of Thin Films on Substrates

Masanori Murakami, Tung-Sheng Kuan, and Ilan A. Blech

I. Introduction	164
II. Biaxial Strain Model	165
III. Strain Relaxation Mechanisms	167
IV. Strain Relaxation by Dislocation Glide	171
V. Strain Relaxation by Diffusional Creep	185
VI. Strain at Grain Boundaries	191
VII. Strain and Stress at Film Edges	194
VIII. Microstructures Which Affect Mechanical Properties of Thin Films	203
IX. Application	207
References	209

PART III. VARIATION OF COMPOSITION OF THIN FILMS

6 Ion Beam Modification of Thin Films

J. M. Poate

I. Introduction	213
II. Range and Energy Deposition	214
III. Sputtering-Induced Compositional Changes	216
IV. Implanted Metastable Phases	221
V. Ion-Beam-Induced Reactions of Metal Films	228
References	235

7 Thin Alloy Films for Metallization in Microelectronic Devices

K. N. Tu

I. Introduction	237
II. Metallurgical Degradation in Microelectronic Devices	239
III. Near-Equilibrium Multilayered Thin-Film Structure	248

CONTENTS	<i>vii</i>
IV. Applications of Thin Alloy Films in Forming Shallow Silicide Contacts	261
V. Conclusion	280
References	281
PART IV. VARIATION OF PATTERN OF THIN FILMS	
8 Fabrication and Physical Properties of Ultrasmall Structures	
<i>R. B. Laibowitz and A. N. Broers</i>	
I. Introduction	285
II. Fabrication	286
III. Physical Properties	298
IV. Summary	309
References	311
INDEX	313
CONTENTS OF PREVIOUS VOLUMES	329